

Materials List for:

Plasmonic Trapping and Release of Nanoparticles in a Monitoring Environment

Jung-Dae Kim¹, Yong-Gu Lee²

¹Division of Scientific Instrumentation, Korea Basic Science Institute (KBSI)

²School of Mechanical Engineering, Gwangju Institute of Science and Technology (GIST)

Correspondence to: Yong-Gu Lee at lygu@gist.ac.kr

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Materials

Name	Company	Catalog Number	Comments
Negative photoresist	MicroChem	SU-8 2075	
Developer	MicroChem	SU-8 Developer	
Positive photoresist	Merck Ltd.	AZ GXR-601	
AZ Photoresist Developers	Merck Ltd.	AZ 300 MIF	
HMDS	Merck Ltd.	AZ Adhesion Promoter	
Aligner	Midas System	MDA 400M	
Atmospheric plasma machine	Atmospheric Process Plasma Co.	IDP-1000	
Polydimethylsiloxane (PDMS)	Dow Corning	Sylgard 184 A/B	
Gold coated test slides	EMF Co.	TA124(Ti/Au)	
Au etchant	Transene Inc.	TFA	
Ti etchant	Transene Inc.	TFT	
40X objective lens	Edmund Optics	40X DIN	
60X water immersion objective lens	Olympus	LUMPLFLN 60XW	
Optical fiber incident laser	IPG Photonic	YLR 10	
SMF coupler	Thorlabs	MBT612D/M	
Syringe micropump	Harvard	PC2 70-4501	
Fluorescent microscope	Olympus	IX-51	
Plasma system	Femto Science Inc	CUTE-MPR	